

IN THE CLAIMS:

Please CANCEL claims 42-45 without prejudice to or disclaimer of the recited subject matter.

Please AMEND claims 37, 40 and 41, and ADD new claims 46-51, as follows. Please note that all claims currently pending in this application are reproduced below for the Examiner's convenience.

1-36. (Canceled)

37. (Currently Amended) An exposure apparatus for performing exposure of a substrate to light via a pattern of a reticle, while the substrate and the reticle are scanned ~~in accordance with a target speed~~, said apparatus comprising:

 a reticle stage configured to hold the reticle and to move;
 a substrate stage configured to hold the substrate and to move;
 an interface configured to input information of a condition of the exposure; and
 a controller configured to select, as an exposure method to be performed, an from
~~a first exposure method in which the exposure is performed while the target speed is constant, and a second exposure method in which the exposure is performed while the target speed is changing~~ said reticle stage and said substrate stage are accelerated, based on the input information.

38. (Previously Presented) An apparatus according to claim 37, wherein the condition of the exposure includes at least one of a shot size, a shot layout of the exposure to be performed, an

alignment measurement value, a shot layout of the exposure having been performed, a shot position, and an accuracy required with respect to moving said reticle stage and said substrate stage.

39. (Previously Presented) An apparatus according to claim 37, wherein the condition of the exposure includes a synchronization accuracy with respect to moving said reticle stage and said substrate stage.

40. (Currently Amended) A method of manufacturing a device, said method comprising steps of:

performing exposure of a substrate to light via a pattern of a reticle using an exposure apparatus ~~as defined in claim 37~~;

developing the exposed substrate; and

processing the developed substrate to manufacture the device,

wherein the exposure apparatus performs the exposure while each of the substrate and the reticle is scanned in accordance with a target speed, the apparatus including:

(i) a reticle stage configured to hold the reticle and to move,

(ii) a substrate stage configured to hold the substrate and to move,

(iii) an interface configured to input information of a condition of the exposure, and

(iv) a controller configured to select, as an exposure method to be performed, an exposure method in which the exposure is performed while the reticle stage and the substrate stage are accelerated, based on the input information.

41. (Currently Amended) An apparatus according to claim 37, wherein said controller is configured to perform the ~~determination selection~~ based on a user's indication if a manual specification mode is specified as a ~~determination selection~~ mode of said controller.

42-45. (Canceled)

46. (New) An exposure apparatus for performing exposure of a substrate to light via a pattern of a reticle, while the substrate and the reticle are scanned, said apparatus comprising:

- a reticle stage configured to hold the reticle and to move;
- a substrate stage configured to hold the substrate and to move;
- an interface configured to input information of a condition of the exposure; and
- a controller configured to select, as an exposure method to be performed, an exposure method in which the exposure is performed while said reticle stage and said substrate stage are decelerated, based on the input information.

47. (New) An apparatus according to claim 46, wherein the condition of the exposure includes at least one of a shot size, a shot layout of the exposure to be performed, an alignment measurement value, a shot layout of the exposure having been performed, a shot position, and an accuracy required with respect to moving said reticle stage and said substrate stage.

48. (New) An apparatus according to claim 46, wherein the condition of the exposure includes a synchronization accuracy with respect to moving said reticle stage and said substrate stage.

49. (New) An apparatus according to claim 46, wherein said controller is configured to perform the selection based on a user's indication if a manual mode is specified as a selection mode of said controller.

50. (New) An apparatus according to claim 46, wherein said controller is configured so that the exposure method selected by said controller is an exposure method in which the exposure is further performed while the reticle stage and the substrate stage are accelerated.

51. (New) A method of manufacturing a device, said method comprising steps of:
performing exposure of a substrate to light via a pattern of a reticle using an exposure apparatus;
developing the exposed substrate; and
processing the developed substrate to manufacture the device,
wherein the exposure apparatus performs the exposure while each of the substrate and the reticle is scanned in accordance with a target speed, the apparatus including:
(i) a reticle stage configured to hold the reticle and to move,
(ii) a substrate stage configured to hold the substrate and to move,
(iii) an interface configured to input information of a condition of the exposure; and
(iv) a controller configured to select, as an exposure method to be performed, an exposure method in which the exposure is performed while the reticle stage and the substrate stage are decelerated, based on the input information.